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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Tradaman Office		Application No. 10/813,453
by A	pplicant	Applicant Richard Schenker et al.	
(Use several s	heets if necessary)	Filing Date March 29, 2004	Group Art Unit 2852

U.S.:Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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	Foreign Patent Documents or Published Foreign Patent Applications							
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	Other Documents (include Author, Title, Date, and Place of Publication)						
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Initial	ID	Document Document					
U	AN	Richard Schenker et al., "Material Limitations to 193-nm Lithographic System Lifetimes", SPIE Vol. 2726, pgs. 698-706					
26	AO	Richard E. Schenker et al., "Ultraviolet-induced densification in fused silica", J. Appl. Phys. 82 (3), August 1, 1997, pgs. 1065-1071					
2	AP	G. de Zwart et al., "Performance of a Step and Scan System for DUV Lithography", SPIE Vol. 3051, pgs. 817-830					
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Attorney's Docket No. 10559-928001

Application No. 10/813,453

Information Disclosure Statement
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Applicant
Richard Schenker et al.

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